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ISSUE CLASSIFICATION	
Class	Subclass

PATENT NUMBER

## U.S. UTILITY Patent Application

 O.I.P.E. SCANNED  G.A. 	PATENT DATE
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APPLICATION NO.	CONT/PRIOR	CLASS	SUBCLASS	ART UNIT	EXAMINER
09/981992		414		3652	

## APPLICANTS

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Wafer handling system and method for use in lithography patterning

[illegible]

<input type="checkbox"/> <b>TERMINAL DISCLAIMER</b>	<b>DRAWINGS</b>		<b>CLAIMS ALLOWED</b>	
	<b>Sheets Dwg.</b>	<b>Figs. Dwg.</b>	<b>Print Fig.</b>	<b>Total Claims</b>
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<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____  _____				
			<b>ISSUE FEE</b>	
			<b>Amount Due</b>	<b>Date Paid</b>
<input type="checkbox"/> The terminal ____months of this patent have been disclaimed.			<b>ISSUE BATCH NUMBER</b>	
	(Legal Instruments Examiner)		(Date)	

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